

	Hits	Search Text
1	231	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immersion near4 liquid) or liquid) same (lithograph\$4 or photolithograph\$4)) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer) same (rotat\$4 or moving or moveable or movement))
2	266	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immersion near4 liquid) or liquid) same (lithograph\$4 or photolithograph\$4)) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer) same (rotat\$4 or motor or driv\$3))

	Hits	Search Text
3	87	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immersion near4 liquid) or liquid) same (lithograph\$4 or photolithograph\$4)) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer) same (rotational or rotating or rotate))
4	8	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$4 near4 liquid) or immers\$4) same (lithograph\$4 or photolithograph\$4)) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer) same (rotational or rotating or rotate) same time)

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5	4	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immers\$4 near4 liquid) or immers\$4 or liquid) near6 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer) same (rotational or rotating or rotate) same time)
6	16	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immers\$4 near4 liquid) or immers\$4 or liquid) near6 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer) same (rotational or rotating or rotate))
7	445	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or liquid or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer))

	Hits	Search Text
8	193	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or liquid or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4) same (substrate or resist or photoresist or wafer)) and ((substrate or wafer) same (rotation or rotational or rotating))
9	52	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or liquid or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4 or post\$3bak\$3 or PEB) same (substrate or resist or photoresist or wafer) same (period or time)) and ((substrate or wafer) same (rotation or rotational or rotating) same (speed or time or period or rpm))
10	66	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (immersion near7 (lithograph\$4 or photolithograph\$4)))

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11	23	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (immersion near7 (lithograph\$4 or photolithograph\$4))) and ((substrate or wafer) same (dry\$3 or heat\$4 or bak\$4)) and ((substrate or wafer) same (spin\$3 or rotate or rotational or rotating or rpm))
12	2	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4 or post\$3bak\$3 or PEB) same (substrate or resist or photoresist or wafer) same (period or time)) and ((substrate or wafer) same (rotation or rotational or rotating) same (speed or time or period or rpm))

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13	2	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((dry\$3 or heat\$4 or bak\$3 or soft\$3bak\$3 or anneal\$4 or post\$3bak\$3 or PEB) same (substrate or resist or photoresist or wafer)) and ((substrate or wafer) same (rotation or rotational or rotating) same (speed or time or period or rpm))
14	2	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((substrate or wafer) same (rotation or rotational or rotating) same (speed or time or period or rpm))
15	90	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4)))

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16	70	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((thermal\$3 or dry\$3 or heat\$4 or anneal\$4 or bak\$4) same (substrate or wafer or workpiece))
17	70	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4))) and ((thermal\$3 or dry\$3 or heat\$4 or anneal\$4 or bak\$4) same (substrate or wafer or workpiece))
18	10	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4 or projection))) and ((substrate or wafer) same (rotation or rotational or rotating) same (speed or time or period or rpm))

	Hits	Search Text
19	10	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4 or projection))) and ((substrate or wafer) same (rotation or rotational or rotating) same (speed or time or period or rpm))
20	5	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same pattern) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4 or projection))) and ((substrate or wafer) same (rotation or rotational or rotating) same (dry\$3 or bak\$4 or heat\$4))
21	5	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4 or projection))) and ((substrate or wafer) same (rotation or rotational or rotating) same (dry\$3 or bak\$4 or heat\$4))

	Hits	Search Text
22	11	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same (expos\$4 or irradiat\$4 or illuminat\$4) same (((immersion near4 liquid) or immers\$4) near7 (lithograph\$4 or photolithograph\$4 or projection))) and ((substrate or wafer) same (rotation or rotational or rotating))
23	54	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable) same (expos\$4 or irradiat\$4 or illuminat\$4) same (immers\$5 or (immers\$4 near2 liquid)) same (lithograph\$4 or photolithograph\$4 or projection)) and ((substrate or wafer) same (rotation or rotational or rotating))
24	68	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same ((immers\$5 near9 (lithograph\$4 or photolithograph\$4 or projection)) or (project\$3 near4 (apparatus or system or align\$4) near5 (immers\$4 or liquid) near6 gap))) and ((substrate or wafer) same (rotation or rotational or rotating or dry\$4 or heat\$4 or bak\$3) same (liquid or fluid or immers\$4))

	Hits	Search Text
25	12	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (liquid near2 immers\$5 near2 (lithograph\$4 or photolithograph\$4 or project\$3)) or (project\$3 near5 (apparatus or system or align\$4) near5 immers\$4 near6 gap)) and ((substrate or wafer) same (post\$3bak\$4 or PEB or (post near3 expos\$4 near4 bak\$4) or dry\$4 or heat\$4 or bak\$3 or thermal\$3) same (liquid or fluid or immers\$4))
26	9	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (liquid near2 immers\$5 near2 (lithograph\$4 or photolithograph\$4 or project\$3)) or (project\$3 near5 (apparatus or system or align\$4) near5 immers\$4 near6 gap)) and ((substrate or wafer) same (post\$3bak\$4 or PEB or (post near3 expos\$4 near4 bak\$4) or dry\$4 or heat\$4 or bak\$3 or thermal\$3) same (photoresist or resist or pattern\$4))

	Hits	Search Text
27	52	((substrate or wafer) same (radiation\$4sensitive or photoresist or resist or photo\$4imageable)) and ((expos\$4 or irradiat\$4 or illuminat\$4) same (liquid near2 immers\$5 near2 (lithograph\$4 or photolithograph\$4 or project\$3)) or (project\$3 near5 (apparatus or system or align\$4) near8 immers\$4)) and ((substrate or wafer) same (post\$3bak\$4 or PEB or (post near3 expos\$4 near4 bak\$4) or dry\$4 or heat\$4 or bak\$3 or thermal\$3) same (photoresist or resist or pattern\$4))